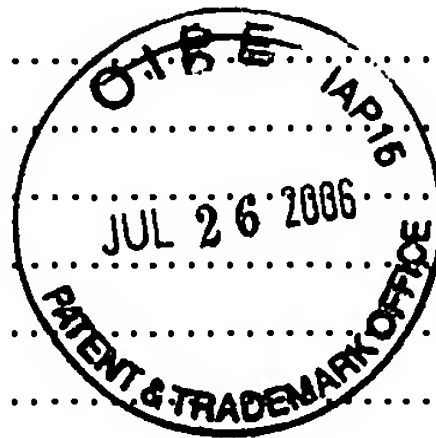


IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 10/655,699
Filing Date September 5, 2003
Confirmation No. 7169
Inventor Garo J. Derderian et al.
Assignee Micron Technology, Inc.
Group Art Unit 2818
Examiner Dung Anh Le
Attorney's Docket No. MI22-2307
Customer No. 021567
Title: Method of Depositing a Silicon Dioxide-Comprising Layer in the
Fabrication of Integrated Circuitry



RESPONSE AFTER JUNE 20, 2006 NOTICE OF ALLOWANCE
PRELIMINARY AMENDMENT TO ACCOMPANY RCE FILING

To: Mail Stop RCE
Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

VIA EXPRESS MAIL

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)
Wells St. John P.S.
601 West First Avenue, Suite 1300
Spokane, WA 99201-3828

Responsive to the Notice of Allowance dated June 20, 2006, Applicant
amends and remarks as follows:

AMENDMENTS